

HIGH ASPECT AND SPACE RATIO SUB-MICRO STRUCTURE FABRICATION WITH MEV PROTON BEAM

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A MeV proton beam writing set-up has been implemented and tested at new Lund Nuclear sub-micron beamline. The beam of 1-0.5 μm size is focused using four Oxford quadrupoles separated in doublets driven by high stability power supplies. The fast beam scanning coils placed in a vacuum chamber writes a pattern of maximum 4096×4096 pixels with a speed of 10 kHz. The samples are placed in a focusing plane 7 cm after the last set of magnets on a sample holder driven by a high precision stepping motor controlled by a computer. The patterns consisting of single pixel lines and dots were irradiated to define the smallest free-standing structure.

2.5 MeV proton beam was used to pattern a lithographic resist and silicon that was after electrochemically etched to reveal structures. The free-standing posts of the size of the beam and aspect ratio $> 20:1$ has been fabricated. Due the absence of a proximity effect the special density, a structure- gap size, of $2:1$ have been achieved. The choice material with good rigidity and adhesion is shown to be of great importance for high aspect and space ratio fabrication, because free-standing structures tend to bend or collapse. Additionally, we present two applications in that are being developed within the project.